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Advancements in Nanofabrication: Innovations in Advanced Semiconductor Materials and Processes for Next-Generation Lithography

Guest Editors:

Dr. Sihai Luo
Department of Chemistry, Faculty of Natural Sciences, Norwegian University of Science and Technology, Trondheim, Norway

Dr. Jingyuan Deng
Department of Chemistry and Chemical Biology, Cornell University, Ithaca, NY 14853, USA

Dr. Chun Cao
School of Mechanical Engineering, Hangzhou Dianzi University, Hangzhou 310018, China

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Message from the Guest Editors

Scope:

We invite contributions that delve into the forefront of nanofabrication technologies, emphasizing advancements in semiconductor materials and processes that directly impact next-generation lithography methods.

Potential Themes:

Advanced Semiconductor Materials: Explore the latest developments in semiconductor materials such as advanced photoresists, high-index materials, and alternative lithographic materials.

Innovative Lithographic Techniques: Investigate novel approaches and methodologies in lithography, including extreme ultraviolet (EUV) lithography, directed self-assembly, and other emerging techniques.

Process Optimization and Integration: Address challenges and breakthroughs in optimizing nanofabrication processes, as well as strategies for the seamless integration of advanced materials into existing fabrication workflows.

Applications in Emerging Technologies: Showcase the practical applications of nanofabrication innovations in areas such as quantum computing, photonics, bioelectronics, and other cutting-edge technologies.

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Special Issue